

March 30, 2004

To: Commissioner of Patents and Trademarks
Washington, D.C. 20231

Fr: George O. Saile Reg. No. 19,572
28 Davis Avenue
Poughkeepsie, N.Y. 12603

Subject:

Continuation of
Serial No.: 09/298,450 4/23/99

LAI-JUH CHEN

CHEMICAL MECHANICAL POLISH PROCESS
CONTROL METHOD USING THERMAL IMAGING OF
POLISHING PAD

PRELIMINARY AMENDMENT

Dear Sir:

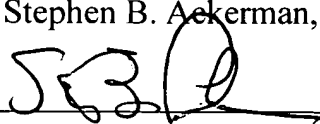
This is a preliminary amendment for the above referenced Continuation. Please
amend the above identified application for patent as follows:

CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States
Postal Service as first class mail in an envelope addressed to: Commissioner of Patents
and Trademarks, Washington, D.C. 20231, on March 30, 2004.

Stephen B. Ackerman, Reg. No. 37,761

Signature/Date



3/30/04

PLEASE AMEND THE SPECIFICATION AS FOLLOWS:

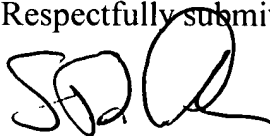
After the title, insert -- This is a continuation of Patent Application serial number 09/298,450, filing date 4/23/99, Chemical Mechanical Polish Process Control Method Using Thermal Imaging Of Polishing Pad, assigned to the same assignee as the present invention, which is herein incorporated by reference in its entirety.

REMARKS

A reference to the parent case has been added by Preliminary Amendment to this Continuation.

The application is believed to be in condition for allowance. Allowance of the subject Patent Application is therefore respectfully requested.

Respectfully submitted,

A handwritten signature in black ink, appearing to read 'SBA', is written over the typed name.

STEPHEN B. ACKERMAN, REG. NO. 37,761